

ABSTRACT OF THE DISCLOSURE

PLASMA CVD APPARATUS AND METHOD FOR MANUFACTURING MAGNETIC
RECORDING MEDIUM

To control, with good uniformity, the thickness of a
5 film to be deposited on a substrate to be deposited. A plasma
CVD apparatus includes a chamber, an anode, a cathode, a
holding part that holds a substrate to be deposited, an inner
shield provided so as to cover spaces between a substrate
to be deposited and each of the anode and the cathode, a magnet
10 disposed outside the inner shield and disposed so as to
surround the inner shield, a first direct current power
source electrically connected to the anode, an alternating
current power source electrically connected to the cathode,
a second direct current power source electrically connected
15 to the substrate to be deposited held by the holding part,
a gas-supplying mechanism for supplying a raw material gas
into the chamber, and an exhaust mechanism for evacuating
the inside of the chamber, and the distance between a plane
that is parallel to a surface of the substrate to be deposited
20 and includes an end part of the magnet on a side of the
substrate to be deposited and a surface of the substrate to
be deposited is from 15 mm to 100 mm.

Figure 1